

|    | Hit<br>s | Search Text  | DBs   |
|----|----------|--|---|
| 29 | 27       | ((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near5 layer))   | US-PGPUB;<br>USPAT; EPO;<br>JPO; DERWENT;<br>IBM_TDB          |
| 30 | 2        | S34 NOT S33  | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 31 | 29       | ((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle or photomask) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near6 (coat\$3 or film or deposit\$3 or layer))) | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 32 | 0        | S36 NOT S34  | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |

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| 33 | 10       | \$4lithograph\$5 and ((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near5 layer))   | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 34 | 4        | ((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) near4 (EUV or (EUV near4 reflective))) and ((photomask or mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al)) and ((mask or reticle or photomask) same ((multi\$4layer near12 reflective) or (multi\$4layer near5 mirror)) same high same low same index same (material or layer)) and (absorb\$4 same (protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) same (thickness\$3 or thick) same (nanometer or nm)) | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |

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|----|----------|---|---|
| 35 | 31       | ((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) near4 (EUV or (EUV near4 reflective))) and ((photomask or mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al)) and ((mask or reticle or photomask) same ((multi\$4layer near12 reflective) or (multi\$4layer near5 mirror))) and (absorb\$4 same (protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide))) same (thickness\$3 or thick) same (nanometer or nm)) | US-PGPUB;<br>USPAT; FPRS;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |